AC PLASMA SOURCE GGK-LF 500

Compact plasma generator 500W@50kHz, sinusoidal.

Integrated measurement system, impedances 500-1000Ω. Ideal for dielectric sputtering and CVD.

Stable discharge, advanced digital control.

Black box generator ideal for those who want to control the power supply via PC or PLC.

The system provides 500 watts at 50 KHz, and impedance can be adjusted from 250 to 1500 ohms.

In some applications, this generator can be used as a replacement for RF, with significantly lower costs and fewer setup problems.

This generator is an ideal alternative to high-voltage DC sources in glow discharge applications.

The discharge is much more stable and there is no formation of localized charges. It can be used for sputtering conductive material targets or for PECVD applications.

Fields of use
Production of PVD and PECVD reactors
Research & Development

Main Applications
Glow discharge (instead of using conventional DC generator)
PECVD deposition process
Generator for small sputtering cathodes
BIAS source for ICP system
Cleaning and activation process via plasma.

TECHNICAL SPECIFICATIONS	
Dimensions	Very compact : 345Dx160Wx120H mm. weight about 4 kg
Connection	Direct electrode connection. No matching network required
Power	Full power of 500Watt available over an impedance range of 1 to 1 without transformer tap adjustment.
Measurament system	Full, accurate measurement built-in system: RMS voltage, DC self bias, power readings available on user port.
Arc detection	Active arc detection and quencing.
Protection	Complete protection circuit: Overtemperature, overvoltge, output power limiting.